



제25회 한국반도체학술대회

The 25th Korean Conference on Semiconductors

2018년 2월 5일(월)-7일(수), 강원도 하이원리조트 컨벤션 호텔

2018년 2월 7일(수), 10:45-12:15

Room C (함백, 5층)

D. Thin Film Process Technology 분과

[WC2-D] Thin Films for Memories and Transistors I

WC2-D-1 10:45-11:00	Dispersion in Ferroelectric Switching Performance of Polycrystalline Hf_{0.5}Zr_{0.5}O₂ Thin Films Seung Dam Hyun, Hyeon Woo Park, Yu Jin Kim, Min Hyuk Park, Young Hwan Lee, Han Joon Kim, Young Jae Kwon, Taehwan Moon, Keum Do Kim, Yong Bin Lee, Beak Su Kim, and Cheol Seong Hwang <i>Department of Materials Science and Engineering, Seoul National University</i>
WC2-D-2 11:00-11:15	ALD W에 기인한 F 이 Oxide 에 미치는 영향 연구 김형철, 이승미, 조홍재, 이안배, 장세억 <i>SK Hynix</i>
WC2-D-3 11:15-11:30	Transient Voltage of Negative Capacitance Depending on Ferroelectric Properties of HfZrO₂. Changyong Oh and Sanghun Jeon <i>Department of Applied Physics, Korea University</i>
WC2-D-4 11:30-11:45	Abnormal Dielectric Properties in High-k/TiO₂ Multilayer Structures Yu Jin Kim, Sehun Kang, Beomyong Kim, Heeyoung Jeon, Kyung Woong Park, and Deok Sin Kil <i>Process Center, SK Hynix</i>
WC2-D-5 11:45-12:00	The Effect of Lanthanide Metal Buffer Layer on the Resistive Switching Cu-Se Based Atomic Switch Hyunsuk Woo and Sanghun Jeon <i>Department of Applied Physics, Korea University</i>
WC2-D-6 12:00-12:15	Arsenic Free Ovonic Threshold Switch (OTS) for 3D Crossbar Memory Selector Myoung Su Seo, Sung Min Kim, Hye Ju Kim, and Sang Woon Lee <i>Department of Energy Systems Research, Ajou University, Department of Physics, Ajou University</i>